



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Patent Application of

Genji Imai et al.

Application No.: 10/627,891

Filed: July 28, 2003

For: POSITIVE SENSITIVE RESIN
COMPOSITION AND A PROCESS
FOR FORMING A RESIST
PATTERN THEREWITH

) **MAIL STOP AF**

) **Group Art Unit: 1752**

) **Examiner: CYNTHIA HAMILTON**

) **Confirmation No.: 3805**

REPLY AND AMENDMENTS PURSUANT TO 37 C.F.R. §1.116

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Sir:

In response to the Office Action [Final Rejection] dated February 22, 2005,
please amend the above-identified patent application as follows:

Enter this Amendment - 4/30/05